

# Aka-Brief #13 Electronic Components

1						→	
	Rhaco Grit P320	Water	300 rpm	25 N	Until plane		
2						→	
	Largan 9	DiaUltra 9 µm	150 rpm	25 N	3:00 min		
3						→	
	Daran	DiaUltra 3 µm	150 rpm	20 N	3:00 min		
4						→	
	Chemal*	Fumed Silica 0.2 µm Alkaline**	150 rpm	10 N	2:00 min		

Times are stated for a 300 mm preparation system and Forces for an individual 40 mm dia. sample.

On a 250 mm system the times should be increased by 30%, on a 200 mm system by 100%.

With larger samples the force should be increased, with smaller samples decreased.

The rotational speed of the head (sample holder or sample mover plate) used is 150 rpm.

Time and Force may vary depending on the equipment.

\* Prior to oxide polishing the polishing cloth should be wetted with water until the holder touches the polishing cloth. For the last 10 seconds of the oxide polishing step, the polishing cloth should be flushed with water to clean both samples and polishing cloth.

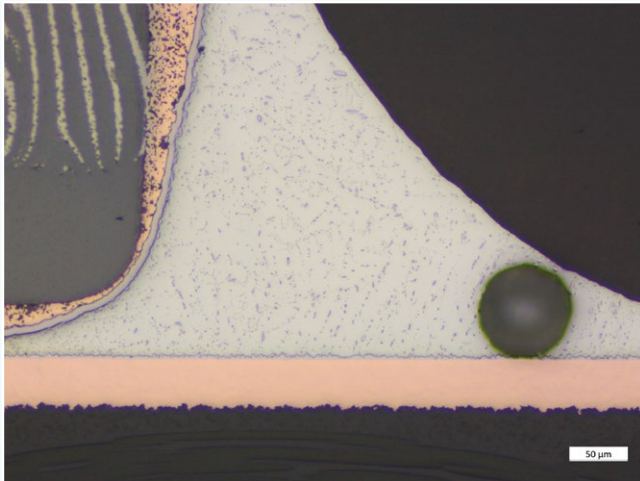
\*\* 96 ml Fumed Silica,  
2 ml H<sub>2</sub>O<sub>2</sub> (30 %),  
2 ml NH<sub>4</sub>OH (25 %).

The mixture should be used fresh (used within a couple of hours).

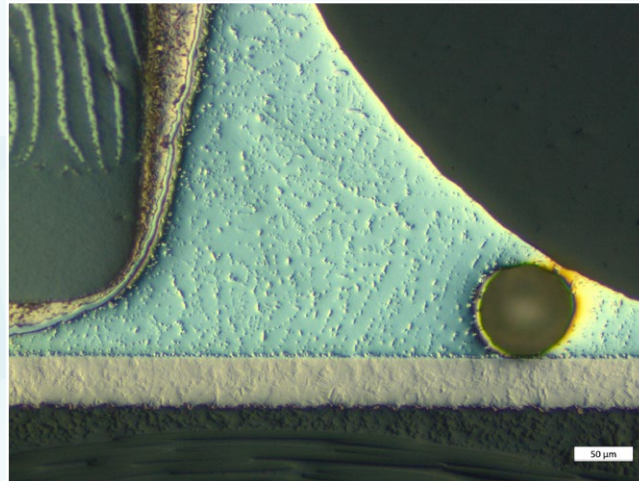


# Aka-Brief #13 Electronic Components

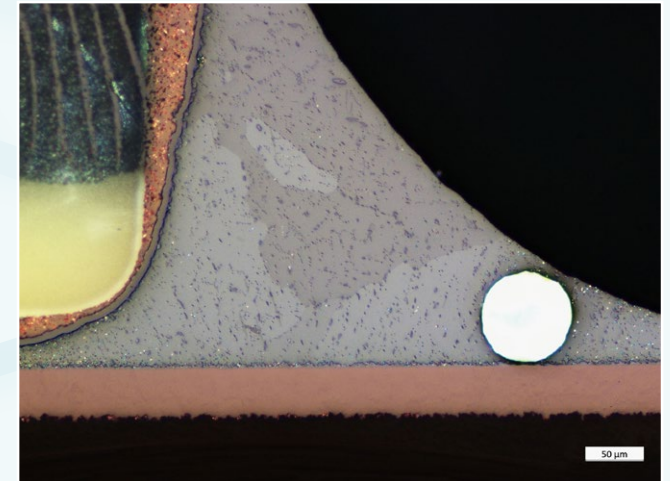
## FINAL RESULT



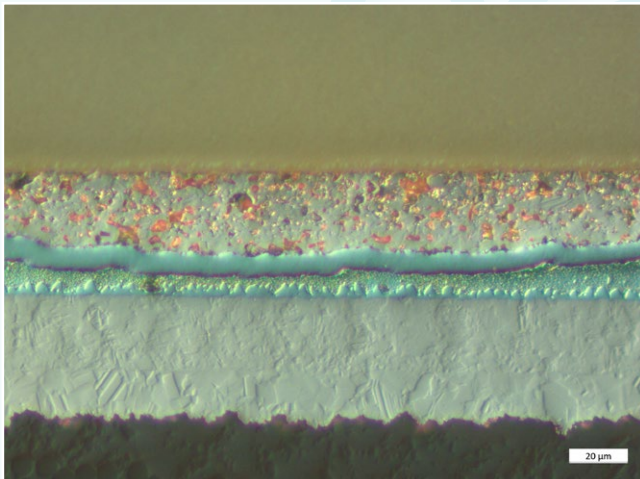
BF, 200x



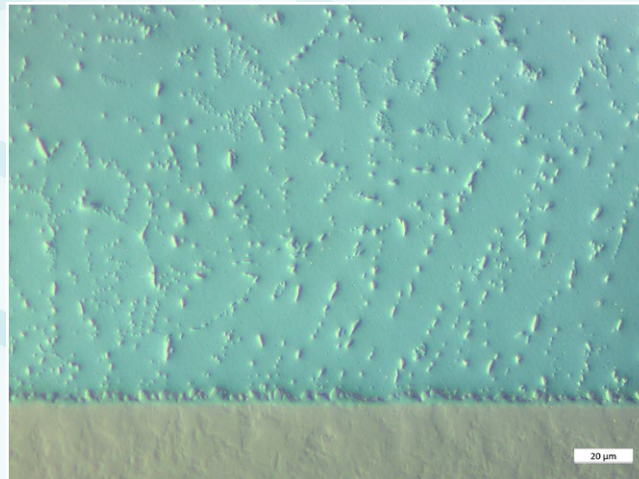
DIC, 200x



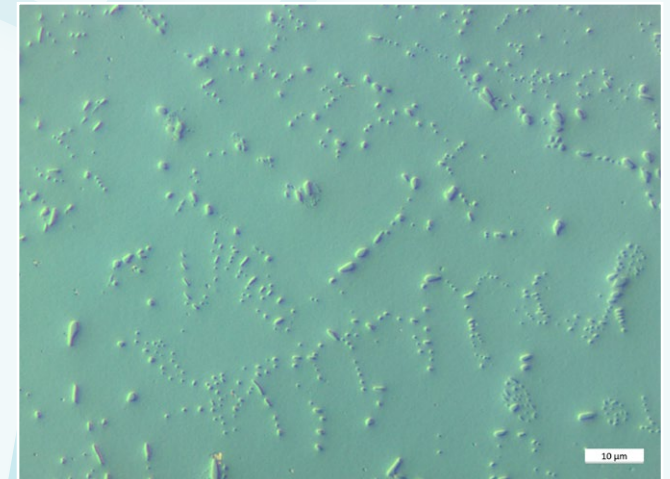
POL + Lambda Compensator, 200x



DIC, 500x



DIC, 500x



DIC, 1000x